

ABSTRACT

INTEGRATED CIRCUIT INDUCTOR

An inductor 101 having a spiral aluminium track 102 deposited on an oxide layer 103 over the silicon substrate 104. The latter is etched away in a trench 114 which extends around the beneath the track, to provide a low dielectric air gap 115. The oxide 103 has an inner region 1031 within the track 102, an outer region 1032 outside the track and a bridging region 1033 extending between the other regions, the bridging region being comprised of intact bridges 1034 and gaps 1035 therebetween, which open to the trench and through which the etchant had access to the silicon substrate for its etching to form the trench.

(Figure 6)